

Supplementary Material (ESI) for Journal of Materials Chemistry

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## Mesoporous Nickel/Carbon Nanotube Hybrid Material Prepared by Electroless Deposition

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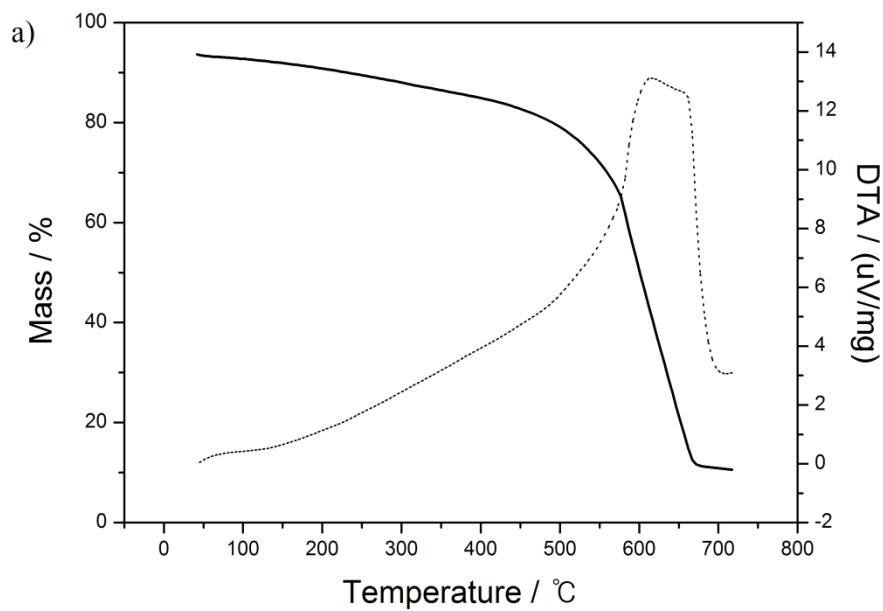
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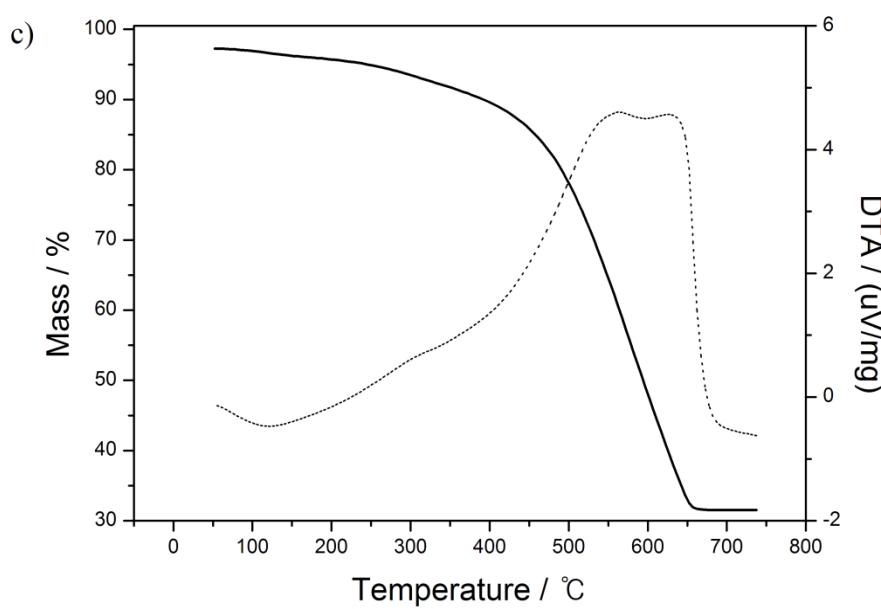
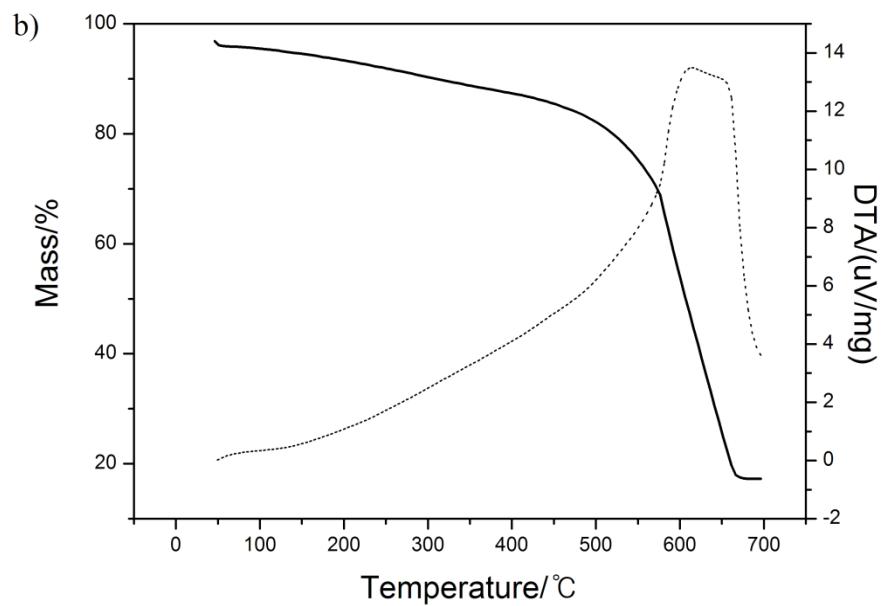
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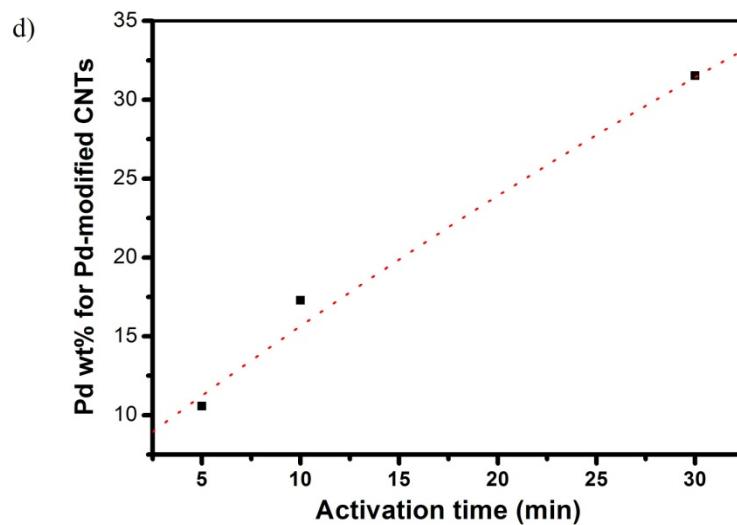
### Supporting Information

S1. TG-DTA plots for Pd-modified CNTs synthesized with activation times of a) 5min. b) 10min. c) 30min. and d) plot of Pd weight % for Pd-modified CNTs vs. activation time.



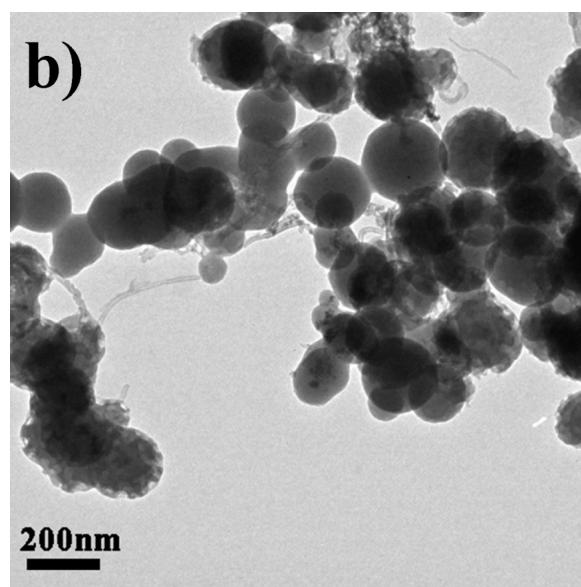
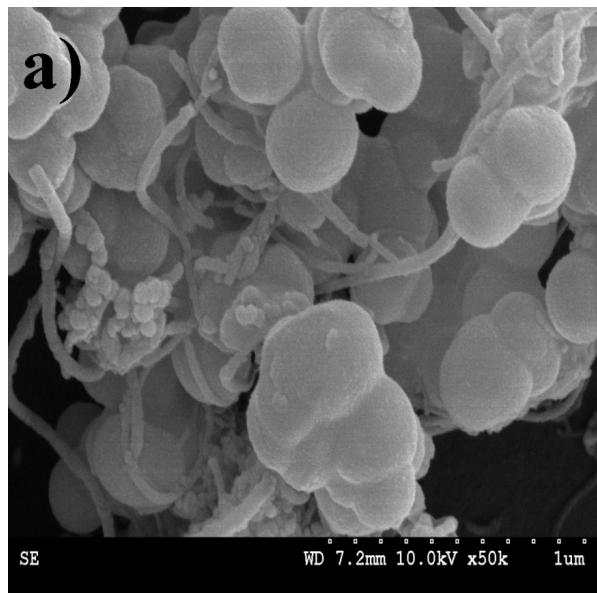


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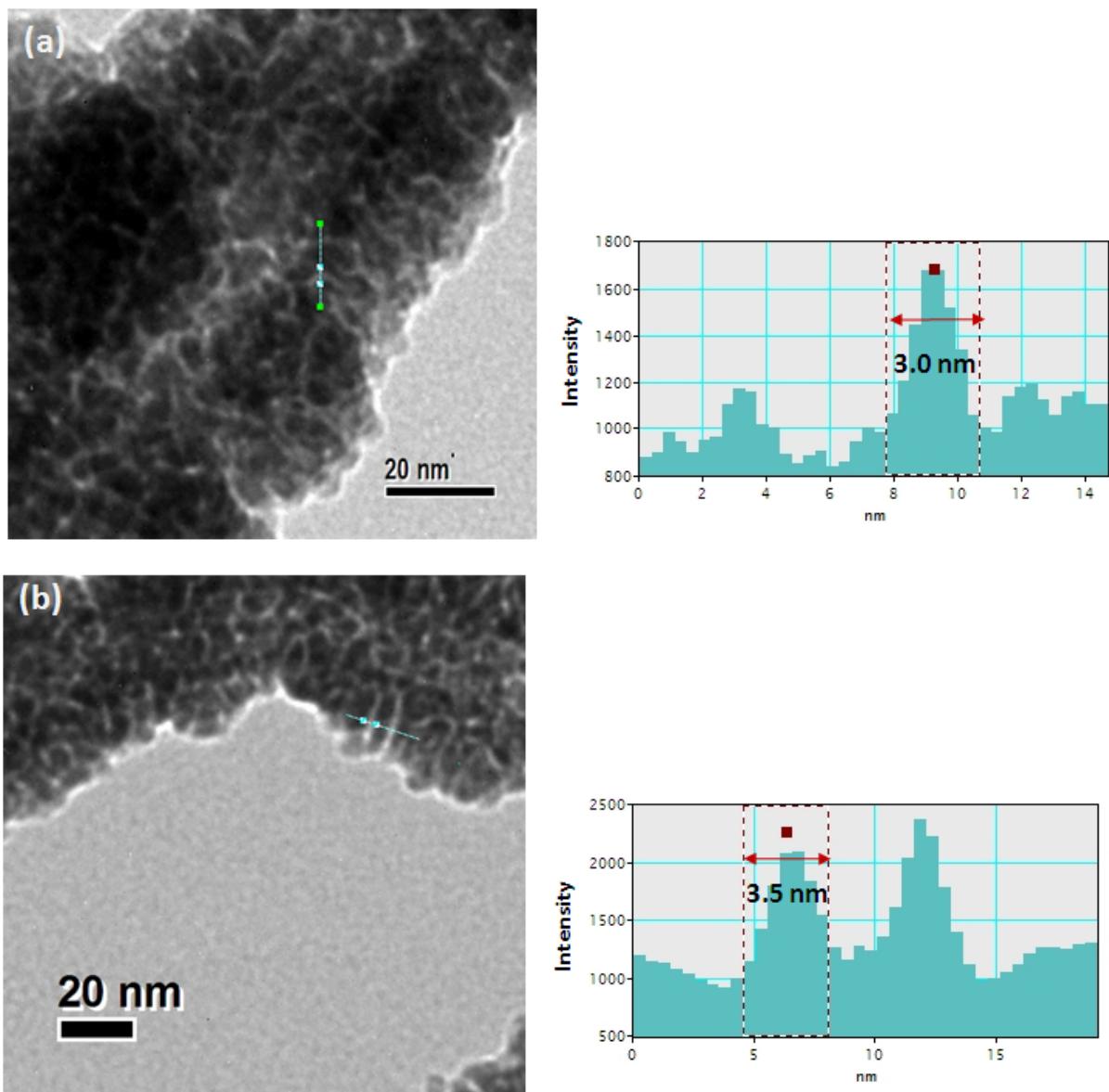


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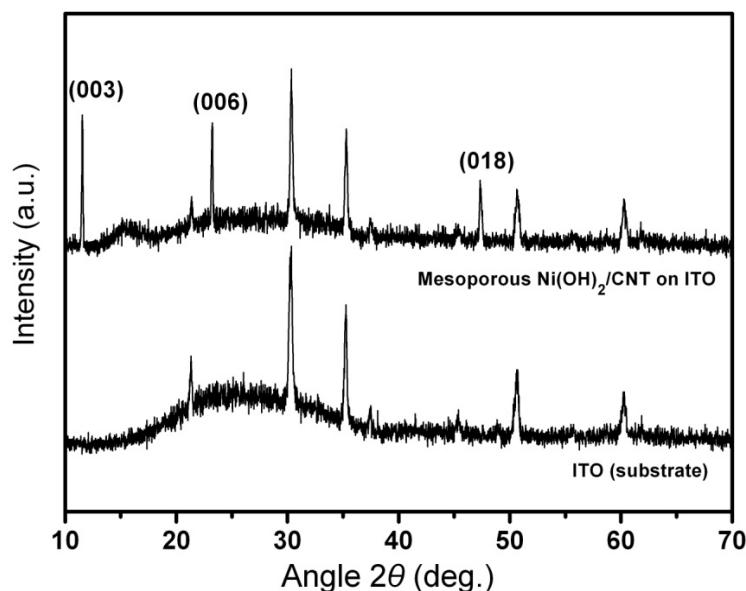
S2. a) FE-SEM and b) TEM images of Ni nanoparticles synthesized through homogeneous nucleation and growth in the solution with Pd catalyst-free CNTs.



S3. TEM image and direct line scanning analysis profile of the mesoporous Ni/CNT nano-hybrid via LLC templating with pore size of (a) 3.0 nm and (b) 3.5 nm.



S4. XRD patterns of mesoporous Ni(OH)<sub>2</sub>/CNT film electrodes.



S4 shows the typical XRD patterns of mesoporous Ni(OH)<sub>2</sub>/CNT film. The XRD patterns of the mesoporous Ni(OH)<sub>2</sub>/CNT film consists of peaks at 11.5°(003), 23.2°(006) and 47.3°(018). Except the substrate peaks, the XRD result corresponds to the  $\alpha$ -nickel hydroxide hydrate (JCPDS no.38-0715).<sup>1</sup>

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S5. Electrochemical properties of nickel oxide based electrode materials prepared by various synthesis routes in the literature.

Material	Synthetic method	Specific capacity	Rate capability	Ref
Porous NiO	LLC templating electrodeposition	146 F g <sup>-1</sup> at scan rate of 10 mV/sec	Decrease of 58 % (from 10 to 100 mV s <sup>-1</sup> )	2
Porous Ni	LLC templating electrodeposition	50 F g <sup>-1</sup> at scan rate of 50 mV/sec	-	3
Mesostructured Ni(OH) <sub>2</sub> film	Micelle template electrochemical deposition	-	-	4
Nanoporous Ni(OH) <sub>2</sub> film	LLC templating electrodeposition	578 F g <sup>-1</sup> at discharging current of 2.5 mA	Decrease of 23% (from 2.5 to 10 mA)	5
Mesoporous NiO film	LLC templating electrodeposition	590 F g <sup>-1</sup> at discharging current of 2.5 mA	Decrease of 31% (from 2.5 to 10 mA)	6
NiO loaded porous carbon	Impregnation (loading amount of NiO: 1 wt.%)	230 F g <sup>-1</sup> at discharging current of 3 mA	-	7
NiO loaded activated carbon	Suspending the activated-carbon in a Ni(NO <sub>3</sub> ) <sub>2</sub> solution (loading amount of NiO: 4.3 wt.%)	196 F g <sup>-1</sup> at discharging current of 10 mA	Decrease of 3% (from 10 to 80 mA)	8
Ni(OH) <sub>2</sub> /activated carbon composite	Physical mixing	540 F g <sup>-1</sup> at discharging current of 1 mA	Decrease of 20% (from 1 to 10 mA)	9
Ni(OH) <sub>2</sub> /activated carbon composite	Chemical precipitation (loading amount of Ni(OH) <sub>2</sub> : 10wt.%)	260 F g <sup>-1</sup> at scan rate of 2 mV/sec	Decrease of 14% (from 2 to 8 mV s <sup>-1</sup> )	10
NiO/MWCNT composite	Chemical impregnation (loading amount of	240 F g <sup>-1</sup> at discharging current of 1mA	-	11

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	NiO: 14 mol%)			
Ni(OH) <sub>2</sub> /MWCNT composite	Hydrothermal synthesis (loading amount of Ni(OH) <sub>2</sub> : 10 wt.%)	432 F g <sup>-1</sup> at scan rate of 10 mVs <sup>-1</sup>	Decrease of 73% (from 10 to 500 mVs <sup>-1</sup> )	12
Ni(OH) <sub>2</sub> /MWCNT composite	Chemical precipitation (loading amount of Ni(OH) <sub>2</sub> : 70wt.%)	303 mAhg <sup>-1</sup> at discharging current of 0.1Ag <sup>-1</sup>	Decrease of 13% (from 0.1 to 0.4 Ag <sup>-1</sup> )	13
Mesoporous Ni(OH) <sub>2</sub> /CNT nano-hybrid	Electroless deposition via selective heterogeneous nucleation and growth (loading amount of Ni: 61wt.%)	306 mAhg <sup>-1</sup> at scan rate of 10 mVs <sup>-1</sup> (equivalent to a discharging current of 22 Ag <sup>-1</sup> )	Decrease of 20% (from 10 to 100 mVs <sup>-1</sup> )	This study

S5 compares the electrochemical properties of the mesoporous Ni/CNT nano-hybrid in this study with mesoporous NiO, mesoporous Ni(OH)<sub>2</sub>, NiO/activated carbon composite, Ni(OH)<sub>2</sub>/activated carbon composite, NiO/CNT composite and Ni(OH)<sub>2</sub>/CNT composite reported in the literature. Xia et al. reported the specific capacity of 303 mAh g<sup>-1</sup> for Ni(OH)<sub>2</sub> in a Ni(OH)<sub>2</sub>/CNT nano-composite at 0.1 A g<sup>-1</sup>, in which Ni(OH)<sub>2</sub> nanoparticles were dispersed on the CNTs with a Ni(OH)<sub>2</sub> loading of 70 wt%.<sup>13</sup> Our mesoporous Ni(OH)<sub>2</sub>/CNT shows the specific capacity of 306 mAhg<sup>-1</sup> for Ni(OH)<sub>2</sub> in the hybrid at much higher charge/discharge rates. It demonstrates that the mesoporous Ni(OH)<sub>2</sub>/CNT nano-hybrid has a great potential as an electrode materials with excellent high rate capability for high rate battery applications.

## Reference

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